Synthesis of In₂O₃ Nanowire-Decorated Ga₂O₃ Nanobelt Heterostructures and **Their Electrical and Field-Emission Properties**

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ABSTRACT We report on the synthesis of In₂O₃ nanowire-decorated Ga₂O₃ nanobelt heterostructures via a simple catalyst-free method. A typical heterostructure, where an In₂O₃ nanowire forms a sort of a "dorsal fin" on the Ga₂O₃ nanobelt, exhibits the T-shaped cross-section. The structure, electrical porperties, and field-emission properties of this material are systematically investigated. The heterostructures possess a typical n-type semiconducting behavior with enhanced conductivity. Field-emission measurements show that they have a low turn-on field (\sim 1.31 V/µm) and a high field-enhancement factor (over 4000). The excellent field-emission characteristics are attributed to their special geometry and good electrical properties. The present In₂O₃-decorated Ga₂O₃ heterostructures are envisaged to be decent field-emitters useful in advanced electronic and optoelectronic nanodevices.

> KEYWORDS: Ga₂O₃ nanobelt · In₂O₃ nanowire · heterostructures · electrical properties · field-emission

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ne-dimensional (1D) semiconductor heterostructured submicrometer/nanometer-scale materials are of prime interest as building blocks in miniaturized electronic and photonic devices.¹ Recently, significant progress has been made in regard to various axial,^{2,3} radial,^{4–8} and branched^{9–12} 1D heterostructure syntheses. In fact, the successful design and controllable growth of composition-modulated heterostructures may lead to enhanced functionalities, such as emission efficiency and high electron mobility.¹³ For example, InAs/InP core/shell nanowire heterostructures have shown a significant increase in electron mobility due to the InP passivation laver.⁷ ZnS nanotube-In nanowire-branched heterostructures have exhibited multiply enhanced field-emission properties due to their special geometry. Branched structures attached on a long backbone and having effectively high aspect ratios have demonstrated remarkably large field enhancement.¹² All these exciting works indicate that a design of novel 1D heterostructures

opens up new wide opportunities not only for fundamental science but also for potential utilizations in diverse functional devices.

Monoclinic gallium oxide (β -Ga₂O₃), one of the transparent conducting oxides, is an important wide band gap material. It becomes an n-type semiconductor when synthesized under reducing conditions due to oxygen vacancies.¹⁴ β-Ga₂O₃ has been considered as a promising material for fabricating optoelectronic devices, spin-tunneling junctions, and gas sensors.^{15–18} Although many studies have been devoted to the synthesis and property investigations of various Ga₂O₃ nanostructures, such as wire-, ribbon-, cable-, and cactus-like structures, 14, 19-23 the analogous reports on 1D Ga₂O₃-based heterostructures have still been lacking. It is believed that the rational synthesis of such heterostructures will allow one to combine different and distinct functionalities of the components and to realize unique properties in such complex systems.

In this paper, we report on the synthesis of 1D In₂O₃-decorated Ga₂O₃ heterostructures where an In₂O₃ nanowire is located on the back of a Ga₂O₃ nanobelt, thus creating a sort of a "dorsal fin". The heterostructures have widths of ~200-500 nm and lengths of up to tens or hundreds of micrometers. Field-effect transistors (FETs) were designed and fabricated based on individual In₂O₃-decorated Ga₂O₃ heterostructures, and their electrical transport properties were then studied. They exhibited a typical n-type semiconducting behavior and a notable enhancement of conductivity. Moreover, the regarded heterostructures possessed excellent field-emission characteristics: a low turn-on field (~1.31

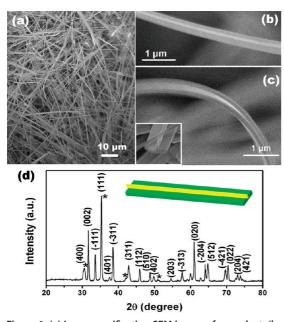


Figure 1. (a) Low-magnification SEM image of a product. (b, c) High-magnification SEM images of an individual heterostructure revealing the T-shaped cross-section (the inset). (d) XRD pattern of the product.

 $V/\mu m$) and a high field-enhancement factor (over 4000). Due to their special geometry and enhanced conductivities the field-emission properties of the present nanomaterials not only surpass those of pure Ga₂O₃ and In₂O₃ components but also rival those of many other prospective 1D nanostructures. The novel structures are envisaged to become highly valuable in field-emitters and electrical and optoelectronic nanodevices.

RESULTS AND DISCUSSION

After the synthesis, wirelike products were found on the copper foil substrate. The product morphology was checked using scanning electron microscopy (SEM). Figure 1a shows a low-magnification SEM image of the material. It contains numerous whiskers with lengths ranging from several tens to hundreds of micrometers. High-magnification images (Figure 1b,c) reveal that a typical whisker, with a diameter of \sim 300 nm and a length of up to \sim 60 μ m, displays a somewhat unusual appearance (see also the Supporting Information, Figure S1). Each heterostructure consists of a nanobelt and the nanowire located on its back forming a sort of a "dorsal fin"; thus, it shows the overall T-shaped crosssection (Figure 1c, inset). Further investigations by transmission electron microscopy (TEM) and X-ray energy dispersive spectroscopy (EDS) suggest that most of the whiskers (more than 80% of the product) are indeed such Ga₂O₃/In₂O₃ heterostructures, where the nanobelts and nanowires are made of Ga₂O₃ and In₂O₃, respectively (shown later). An X-ray diffraction (XRD) pattern of a product is shown in Figure 1d. Most of the strong peaks can be indexed to a monoclinic structure of Ga₂O₃ (JCPDS 76-573). Besides those peaks, some

small peaks marked with star symbols are attributed to a cubic In_2O_3 phase (JCPDS 6-416).

The product morphology and microstructures were thoroughly studied using TEM, EDS, and selected area electron diffraction (SAED). Figure 2a is a typical TEM image of an individual heterostructure with a uniform width of 250 nm. The heterostructure appears to exhibit an inner "core" with a diameter of \sim 50 nm. In fact, the inner "core" of a dark contrast in TEM images actually represents the protuberant "dorsal fin" region along the axial direction. EDS spectra collected from the center and edge of the heterostructures (Figure 2b,c) show that the centers are composed of Ga, In, and O, whereas the edge only contains Ga and O. The SAED pattern of the heterostructure (Figure 2a, inset) can be indexed to the [110] zone axis of β -Ga₂O₃ and [121] zone axis of In₂O₃. Thus, the crystallographic relationship is that the [110] zone axis of a Ga_2O_3 belt is parallel to the [121] zone axis of an In₂O₃ wire. Figure 2d is a high-resolution TEM image taken from the edge of the Ga₂O₃ nanobelt. It clearly shows a single-crystalline characteristic. The d spacings of 0.267 and 0.282 nm correspond well to the (-111) and (002) plane separations in Ga₂O₃, respectively. The upper-right inset displays the corresponding 2D-Fourier transform (FFT) pattern. All reflections can be assigned to the [110] zone axis of a β -Ga₂O₃. An HRTEM image taken from the interface region of the Ga₂O₃ nanobelt/In₂O₃ nanowire is shown in

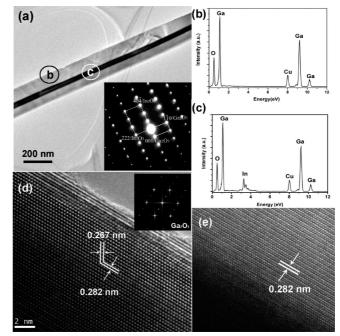


Figure 2. (a) Typical TEM image of a heterostructure; (inset) the corresponding SAED pattern, revealing the crystallographic relationship between a Ga_2O_3 nanobelt and the ln_2O_3 nanowire. (b,c) EDS spectra taken from the labeled regions, showing that the center is composed of Ga, In, and O, whereas the edge only contains Ga and O. (d) HRTEM image recorded from the edge of the nanobelt implying its single-crystalline character; (inset) an FFT pattern corresponding to the HR-TEM image in panel (d). (e) HRTEM image taken from the nanobelt/ nanowire interface region.

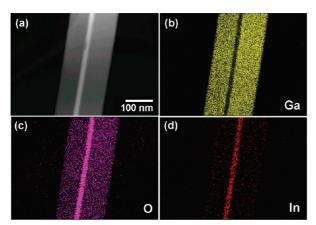
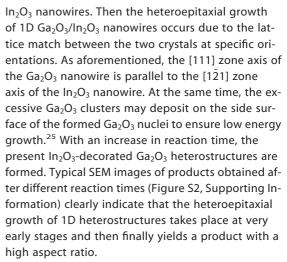


Figure 3. (a) HAADF STEM image of a heterostructure. (b-d) The spatially resolved Ga, In, and O elemental maps.

Figure 2e. The nontransparent dark region can be attributed to an impermeability of the 300 kV electron beam, indicating that a thickness of the protuberant heterostructure region is more than 100 nm.

A detailed chemical analysis was carried out using high-angle annular dark-field (HAADF) scanning transmission electron microscopy (STEM) and EDS elemental mappings. Figure 3a presents a HAADF STEM image of a heterostructure. The clear bright contrast regions naturally reflect the spatial distribution of In species (In has a larger atomic number than Ga). The elemental maps displayed in Figure 3b-d shed light on the distribution of the constituting elements, which are Ga, In, and O. The strong In L-edge signal originates from the In₂O₃ wire. The results clearly demonstrate a well-defined compositional profile of the Ga₂O₃/In₂O₃ heterostructure.

The formation of an In_2O_3 -decorated Ga_2O_3 heterostructure proceeds via a one-step vapor solid (VS) growth process. The whole growth process can be proposed as shown in Figure 4. At a high temperature, the reaction between Ga_2O_3 and activated carbon takes place as follows: Ga_2O_3 (solid) + 2C (solid) $\rightarrow Ga_2O$ (vapor) + 2CO (vapor) and 2Ga_2O (vapor) + 4CO (vapor) $\rightarrow 4Ga$ (vapor) + C (solid) + 3CO₂ (vapor).²⁴ The newly generated Ga or Ga_2O vapors mix with the In vapor (coming from the starting material) and reach the substrate surface. Through the reaction with residual oxygen in the reaction system, Ga_2O_3 and In_2O_3 clusters are simultaneously formed and act as the nuclei for Ga_2O_3 and



Field-effect transistors (FETs) based on individual In₂O₃-decorated Ga₂O₃ heterostructures were fabricated, and their electrical properties were studied. The parallel Ti/Au electrodes, \sim 3 μ m apart, were fabricated on a single heterostructure, as shown in Figure 5a. Figure 5b presents the gate-dependent drain-source current (I_{ds}) versus voltage (V_{ds}) curves recorded on a representative single FET device. The FET device exhibits notable gate dependence and is conductive, reaching a current of 3.4 μA with a V_{ds} of 10 V and a gate voltage (V_{a}) of 40 V. The nonlinear curves indicate that Schottky barriers form between the Ti/Au electrodes and the heterostructure. With a positively increasing V_{a} $(-40 \text{ V} \rightarrow 40 \text{ V})$, the conductance of the heterostructure increases, revealing an n-type conductivity. It has been reported that the pure Ga₂O₃ nanowires are normally n-type semiconductors due to oxygen vacancies.¹⁴ In this work, the In₂O₃-decorated Ga₂O₃ heterostructures exhibit similar n-type semiconducting behavior. In addition, we also studied the electrical properties of the fabricated devices at different temperatures, in vacuum. Figure 5c displays $I_{ds} - V_{ds}$ curves measured from 300 to 10 K with $V_{q} = 0$ V. It can be seen that the conductance of a device decreases as the temperature decreases.

We further estimate the carrier concentration and mobility in the heterostructures. The conventional method to obtain such parameters is to analyze its field-effect behavior using a FET setup. However, herein the Schottky barriers play an important role in the electron transport and the FET model may

> result in an underestimate of the mobility.²⁶ In fact, the present device, as a metal—semiconductor—metal (MSM) structure, can be modeled by two Schottky barriers connected back to back, in series, with a resistor in between. Considering the tunneling current to become

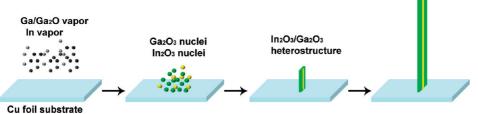


Figure 4. Schematic diagram of the growth of In₂O₃-decorated Ga₂O₃ heterostructures.

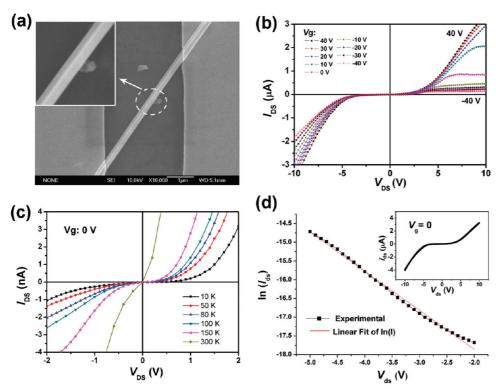


Figure 5. (a) SEM image of an In_2O_3 -decorated Ga_2O_3 heterostructure-based FET; (inset) high-magnification SEM image showing the morphology of the heterostructure. (b) $I_{ds}-V_{ds}$ plots at different V_{g} . (c) $I_{ds}-V_{ds}$ curves measured from 300 to 10 K with $V_g = 0$ V. (d) Experimental and fitted In/vs V plots at an intermediate bias using the $I_{ds}-V_{ds}$ curve at $V_g = 0$ (inset).

dominant under a reverse bias in a low-dimensional system, thermionic field emission theory is proposed for analyzing the present semiconductor parameters from the two-terminal I-V curves.^{26,27} In detail, the reverse-biased Schottky barrier dominates the total current *I* in the intermediate bias regime of the $I_{ds}-V_{ds}$ curve ($V_g = 0$)

$$\ln I = \ln(SJ) = \ln S + V\left(\frac{q}{kT} - \frac{1}{E_0}\right) + \ln J_S$$

where J is the current density through the Schottky barrier, S is the contact area, J_S is a slowly varying function of an applied bias, and $E_0 = E_{00} \operatorname{coth}(qE_{00}/kT)$ with $E_{00} = \hbar/2[n/(m_n^*\varepsilon_S\varepsilon_0)]^{1/2}$, n is electron concentration, m_n^* and ε_S are the effective mass of an electron and relative permittivity of the material, respectively, and ε_0 is the permittivity of free space.

The logarithmic plot of a current *I* as a function of a bias *V* gives approximately a straight line with a slope $q/(kT) - 1/E_0$, as shown in Figure 5d. Then *n* can be obtained via E_0 , and the electron mobility can be calculated using $\mu = 1/(nq\rho)$, with ρ being the resistivity of the heterostructure, which can be estimated to be 0.5 $\Omega \cdot \text{cm}$. Applying this procedure to the *I*-*V* curves and assuming the relevant physical constants, such as m_n^* and ε_S (for Ga₂O₃, $m_n^* \approx 0.342 m_e$, $\varepsilon_S \approx 10$; for In₂O₃, $m_n^* \approx 0.3 m_e$, $\varepsilon_S \approx 8.9$, m_e being the free electron mass²⁸⁻³⁰), the electron concentration of the heterostructure is estimated to be $(4.3-5.5) \times 10^{17} \text{ cm}^{-3}$, and

the electron mobility is calculated to be 23–29 cm² V⁻¹ s¹⁻. We also fabricated standard Ga₂O₃ nanobelts under the same reaction conditions but without the use of In reactant and studied their electrical properties (Supporting Information, Figure S3). The resistivity, electron concentration, and mobility in the synthesized Ga₂O₃ nanobelts was estimated to be 10.87 $\Omega \cdot cm$, 1.77 imes 10¹⁷ cm⁻³, and 3.2 cm² V⁻¹ s¹⁻, respectively. It clearly indicates that the In₂O₃/Ga₂O₃ heterostructures possess significantly lower resistivity (0.5 $\Omega \cdot cm$) (higher conductivity) compared with pure Ga₂O₃ nanobelts (10.87 $\Omega \cdot cm$) as well as Ga₂O₃ nanowires (300-500 $\Omega \cdot cm$) in ref 14. In addition, the electron concentration in an In₂O₃/Ga₂O₃ heterostructure is much higher than in a pure Ga₂O₃ nanobelt. The present carrier mobility in the In₂O₃/Ga₂O₃ heterostructures (23-29 cm² V^{-1} s¹⁻) is about 1 order of magnitude higher than in a standard Ga_2O_3 nanobelt (3.2 cm² V⁻¹ s¹⁻) and is also larger than in normal Ga₂O₃ nanowires (6.54 cm² V⁻¹ s¹⁻) in ref 31. Therefore, on the basis of the above comparison, it is believed that the electrical behavior of the present heterostructures is greatly modulated by the In₂O₃ nanowire decoration. In particular, the In₂O₃ nanowires likely participate in the electron transport together with the Ga₂O₃ nanobelts. In addition, the trace amounts of In dopants into Ga₂O₃ nanobelts as well as the interface effect within the heterostructure may also contribute to the present electrical conductivity. Although the detailed electrical transport mechanism is

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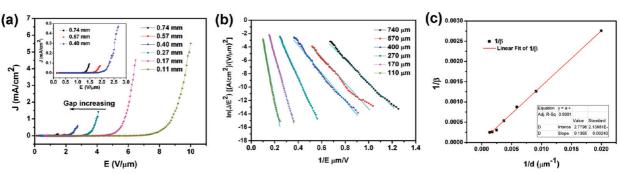


Figure 6. Field-emission properties of the heterostructures. (a) Field-emission current density versus an applied field (J-E) curves and (b) corresponding Fowler–Nordheim (FN) plots with different vacuum gaps. (c) Relationship between the field-enhancement factor, β , and a vacuum gap, *d*. The straight line is the linear fit of the experimental data based on the TRFE model.

still needs further clarification, what we can conclude at present is that, in contrast with standard Ga₂O₃ nanostructures, the present Ga₂O₃-based heterostructures demonstrate an enhancement of electron mobility and conductivity. It has been reported that nanostructures with lower resistivity have a better field-emission performance, which is due to the better supply of electrons to the emitting surface.³² Therefore, the electrical study results imply that the heterostructure may be a valuable field emitter.

In order to study the performance of the In₂O₃decorated Ga₂O₃ heterostructures as a field emitter, field-emission properties were measured in a high vacuum of \sim 4.0 \times 10⁻⁶ Pa. Figure 6a shows the emission current density as a function of the electrical field (J-E plot) measured at different spacings (d) between the anode and a sample. When the gap is increased from 0.11 to 0.74 mm, the turn-on field (E_{to}), which is defined as the field required to produce a current density of 10 μ A/cm², decreases monotonously from 6.45 to 1.31 V/ μ m (Table 1). The current density at 6.4 V/ μ m is as high as 4.5 mA/cm² at d = 0.17 mm, and no current saturation is observed. It worth noting that the much lower turn-on field and higher current density of fieldemission have been obtained for the present heterostructures, compared with either pure Ga₂O₃ nanostructures^{14,21,23} or In₂O₃ nanostructures,^{33,34} as summarized in Table 2. The data suggest that the newly prepared material is a highly valuable field-emitter that rivals previously reported ZnO, ZnS, SiC, Si, and AIN nanowires/nanobelts.35

The field-emission current-voltage characteristics were further analyzed using the Fowler-Nordheim (FN) theory

$$J = (A\beta^2 E^2 / \phi) \exp(-B\phi^{3/2} / \beta E)$$

TABLE 1. Turn-on Field (Eto) and Field-Enhancement Factor
eta Obtained at Different Vacuum Gaps (<i>d</i>)

<i>d</i> (mm)	0.11	0.17	0.27	0.40	0.57	0.74
E _{to} (V/μm)	6.45	4.23	2.89	1.975	1.7	1.31
β	793	1142	1875	3287	3827	4002

$$\ln(J/E^2) = \ln(A\beta^2/\phi) - B\phi^{3/2}/\beta E$$

where $A = 1.54 \times 10^{-6}$ A eV V⁻², $B = 6.83 \times 10^3$ eV^{-3/2} V μ m⁻¹, β is the field-enhancement factor, and ϕ is the work function of an emitting material. Figure 6b shows the FN plots with different vacuum gaps. The plots are approximately linear, indicating that the FN theory well fits the field-emission behavior of the sample. We can calculate β from the slope of the FN plots in Figure 6b. Considering that the work function of Ga₂O₃ is 4.8 eV, β increases from 793 to 4002 under an increasing vacuum gap from 0.11 to 0.74 mm (Table 1). The β value is significantly larger than for other reported Ga₂O₃ or In₂O₃ nanostructures, as also illustrated in Table 2.

β is an important parameter in describing field emission. Generally, the β values are related to the emitter geometry, crystal structure, vacuum gaps, and spatial distribution of emitting centers. Structures with a higher aspect ratio would exhibit stronger field emissions from a given nanostructured material.^{35,36} The relationship between β and d is crucial for fabrication field-emission devices. Figure 6c is a relationship of 1/β and 1/d. It shows that β obviously depends on d with a relationship of $1/β \propto 1/d$. On the basis of the two-region field-emission model, we found that the experimental data are almost fitted to a straight line and can be approximated by $1/β = h/d + 1/β_0$, where h is a

TABLE 2. Comparative Key Field-Emission Performance Parameters of the Present Heterostructures and the Conventional Ga_2O_3 and In_2O_3 Nanostructures Reported in the Literature^{*a*}

material	turn-on field (V/ μ m)	β	ref
quasi-aligned Ga2O3 nanowires	6.2	880	14
$Ga_2O_3 - C$ nanocables	7.73		21
cactus-like Ga ₂ O ₃ nanostructures	12.6	38.2	23
In ₂ O ₃ nanowires	2.47 at 0.1 μ A/cm ²	1810	33
In ₂ O ₃ nanowires	7 and 10.7 at 1 μ A/cm ²		34
In ₂ O ₃ /Ga ₂ O ₃ heterostructures	1.31-6.45	793-4002	this work

^{*a*}Here, the turn-on field is defined as the field required to produce a current density of 10 μ A/cm². If the other values are used, then this is mentioned separately.

or

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width of the field-emission region near the whisker surface and β_0 is the absolute amplification factor, which is intrinsically determined by the emitting surface and independent of *h*, and *d* is an applied voltage. By fitting the slope and intercept value, the *h* and β_0 can be determined as ~136 nm and ~4 × 10⁴, respectively. The value of β_0 is remarkably larger than that of a CNT on an Fe tip ($\beta_0 = 2.5 \times 10^4$) or a CNT film growing on a Si wafer ($\beta_0 = 7900$),³⁷ ZnO nanorods grown on a Si substrate ($\beta_0 = 3738$),³⁸ and aligned CdS nanocone arrays ($\beta_0 = 4933$),³⁶ indicating excellent field enhancement in the present In₂O₃-decorated Ga₂O₃ structures.

The high field-enhancement and low turn-on field values indicate that the present In_2O_3 -decorated Ga_2O_3 heterostructures, despite their submicrometer dimensions, possess excellent field-emission characteristics. As we discussed above, the improved electrical properties (increased conductivity and mobility) are important for the observed field emission behavior. We can conclude that a high aspect ratio, good crystallinity, special geometry, and enhanced conductivity are responsible for these field-emission characteristics. It is believed that the growth of the analogous heterostructures.

tures with reduced dimensions will be an effective route to further enhance their field-emission performance and obtain more efficient emitters.

CONCLUSIONS

Novel 1D In₂O₃-decorated Ga₂O₃ heterostructure whiskers were synthesized via a simple catalyst-free vaporsolid method. The heterostructure consists of a primary Ga₂O₃ nanobelt and the In₂O₃ nanowire (in a shape of a "dorsal fin") and as a whole displays the T-shaped crosssection. Field-effect transistors were fabricated based on individual In₂O₃/Ga₂O₃ heterostructures. These showed n-type characteristics. The heterostructures possess lower resistivity and higher electron mobility compared with pure Ga₂O₃ nanostructures. Field-emission measurements showed the remarkably low turn-on field of ca. 1.31 V/ μ m at a current density of 10 μ A/cm² and a vacuum gap of 0.74 mm. The field-enhancement factor β was calculated to be over 4000. The excellent field-emission characteristics are attributed to a high aspect ratio, good crystallinity, special geometry, and high conductivity of the present heterostructures. This new material may have a high promise for novel field-emitting, electronic and optoelectronic nanodevices.

METHODS

The synthesis of ln₂O₃/Ga₂O₃ heterostructures was carried out in a conventional horizontal furnace. A mixture of Ga₂O₃ (500 mg), ln (100 mg), and activated carbon (50 mg) was put in a quartz boat. A copper foil (10 mm \times 20 mm) was first cleaned using alcohol in an ultrasonic cleaner and then capped on the quartz tobat horizontally. After the boat was transferred into a quartz tube mounted in the furnace, the system was purged with 200 sccm Ar gas for 1 h. Then the furnace was heated to 1000 °C in 30 min and kept at this temperature for 1 h with the Ar flow kept constant. After the system was cooled to room temperature, a brown product was found deposited onto the Cu substrate.

An as-prepared product was characterized by a scanning electron microscope (SEM, JEOL, JSM-6700F), a powder X-ray diffractometer (XRD, RIGAKU, Ultima III, 40 kV/40 mA with Cu K α radiation), a 300 kV high-resolution field-emission transmission electron microscope (TEM, JEOL, JEM-3000F) equipped with an energy-dispersive X-ray analyzer (EDX), and a high-angle annular dark-field scanning transmission electron microscopy detector (HAADF-STEM) (JEOL JEM-3100FEF).

For the fabrication of FET, In_2O_3 -decorated Ga_2O_3 heterostructures were first dispersed in alcohol and then deposited onto a thermally oxidized Si substrate covered with a 600 nm SiO₂ layer at a desired density. The Ti/Au (10 nm/100 nm) interdigitated electrodes were patterned on top of the heterostructures using optical lithography with the assistance of a predesigned mask and electron beam deposition.

The field-emission properties were studied at room temperature in a high vacuum chamber (3 \times 10⁻⁶ Pa) using a 1 mm² crosssectional area Al anode. A dc voltage sweeping from 100 to 1100 V was applied to the samples.

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